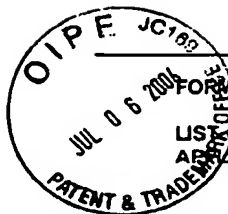


ALL REFERENCES CONSIDERED EXCEPT WHERE LINED THROUGH. /RC/



10822064 GAN: PATENT APPLICATION

Sheet 1 of 8

FORM PTO-1449

LIST OF PATENTS AND PUBLICATIONS FOR
APPLICANT'S INFORMATION DISCLOSURE
STATEMENT

(Use several sheets if necessary)

ATTY. DOCKET NO.

200312670-1

APPLICATION NO.

10/822,064

CONFIRMATION NO.

APPLICANT

Meyer, et al.

FILING DATE

04/08/2004

GROUP

REFERENCE DESIGNATION

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EXAMINER INITIAL		DOCUMENT NUMBER	PUBLICATION DATE	NAME	Pages, Columns, Lines Where Relevant Passages or Figures Appear
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	1C	5985084	11/16/1999	Summersgill, et al. 65	
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/RC/	1L	WO96/35971	11/14/1996	Epigem Limited	WO 9635971	
/RC/	1M	WO01/11591	02/15/2001	Epigem Limited		
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	1P					

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/RC/	1Q	"High-resolution soft lithography"; IBM Zurich Research Laboratory, Science & Technology, Microcontact processing; http://www.zurich.ibm.com/st/microcontact/highres/ .
/RC/	1R	"Replica Molding (REM)"; Lithotemplate.html.; http://www.ee.washingtn.edu/research/microtech/cam/CAMreplicamolding.html .
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EXAMINER

/Rick Chang/

DATE CONSIDERED